

TECHNICAL DATA SHEET

## Levon<sup>™</sup> DM200-SE Enclosed Benchtop Spin Developer

Fully enclosed spin developer • 20–3,000 rpm (no load) • fragments to 8-inch wafers • 100 programs



### Levon<sup>™</sup> DM200-SE Enclosed Benchtop Spin Developer — Representative Configuration

The Levon<sup>™</sup> DM200-SE Enclosed Benchtop Spin Developer is a fully enclosed spin developer with a Teflon-coated stainless steel interior and an anti-corrosion housing. Image shown for reference; final configuration is confirmed in the quotation.

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## SECTION I

## Product Overview

Levon™ DM200-SE Enclosed Benchtop Spin Developer is a fully enclosed spin developer for substrates from fragments to 200 mm (8-inch) wafers, with a spin speed of 20–3,000 rpm (no load), an acceleration of 20–10,000 rpm/s (no load) and 100 customizable programs.

The DM200-SE has a 3-channel developer configuration, including one rinse channel and one nitrogen drying channel. It has a Teflon-coated stainless steel interior, an anti-corrosion housing with a non-stick surface, and a built-in filter for pump protection. Vacuum pressure is adjustable with live monitoring, and liquid delivery and recovery (suction) are adjustable. Tailored options include 4-channel configurations or custom wafer sizes.

## SECTION II

## Core Advantages

- **Fully enclosed development** Fully enclosed development chamber.
- **Teflon-coated interior** Teflon-coated stainless steel interior.
- **Vacuum control** Adjustable vacuum pressure with live monitoring.
- **3-channel developer** 1 × rinse and 1 × nitrogen drying channel within a 3-channel configuration; 4-channel configurations are available as a tailored option.
- **Anti-corrosion housing** Anti-corrosion housing with a non-stick surface.
- **Pump protection** Built-in filter for pump protection.
- **Flow and suction adjustment** Adjustable liquid delivery and recovery (suction).
- **100 customizable programs** Single-step or multi-step mode with 100 customizable programs.

## SECTION III

## Specifications

### Technical data — DM200-SE

| Specifications       |                                                               |
|----------------------|---------------------------------------------------------------|
| Parameter            | Specification                                                 |
| Brand                | Levon™ by ACS Material                                        |
| Product Name         | Levon™ DM200-SE Enclosed Benchtop Spin Developer              |
| Model                | DM200-SE                                                      |
| SKU #                | LVDM2000                                                      |
| Product type         | Spin developer                                                |
| Supported wafer size | From fragments to 200 mm (8-inch wafer)                       |
| Spin speed           | 20–3,000 rpm (no load)                                        |
| Speed resolution     | ±1 rpm                                                        |
| Spin acceleration    | 20–10,000 rpm/s (no load)                                     |
| Recipe time setting  | 0–3,000 s per step; time setting precision 0.1 s              |
| Maximum spin time    | 30,000 s                                                      |
| Spin time resolution | 0.1 s                                                         |
| Programs             | Single-step or multi-step mode with 100 customizable programs |
| Developer channels   | 3 channels, including 1 × rinse and 1 × nitrogen drying       |
| Development chamber  | Fully enclosed                                                |
| Interior             | Teflon-coated stainless steel                                 |
| Housing              | Anti-corrosion housing with non-stick surface                 |
| Pump protection      | Built-in filter for pump protection                           |
| Vacuum control       | Adjustable vacuum pressure with live monitoring               |
| Flow and suction     | Adjustable liquid delivery and recovery                       |
| Tailored options     | 4-channel configurations or custom wafer sizes                |

## Technical data — DM200-SE (continued)

| Specifications         |                         |
|------------------------|-------------------------|
| Parameter              | Specification           |
| Dimensions [W × D × H] | 550 × 600 × 405 mm      |
| Weight                 | 35 kg                   |
| Packing                | Packed in a wooden case |
| Warranty               | 1-year product warranty |

## Scope of delivery

- **Standard configuration:** one DM200-SE main unit, packed in a wooden case.
- **Tailored options, not included** — 4-channel configurations or custom wafer sizes (quoted on request).

## SECTION IV

## Applications

For enclosed spin development of substrates from fragments to 200 mm (8-inch) wafers, with programmable spin speed (20–3,000 rpm, no load), single-step or multi-step programs and rinse and nitrogen drying channels. The DM200-SE is designed for compact semiconductor research.

Product value: fully enclosed development, 20–3,000 rpm (no load), 100 customizable programs and a 3-channel configuration, with 4-channel and custom wafer-size options.

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